

**Table 1**

Experimental conditions of channel doping  
with respect to the silicon-containing amorphous semiconductor film

substrate No.	chemical oxide film	diborane dilution ratio
1	None	0.1%B2H6/H2
2	Exist	0.1%B2H6/H2
3	None	1.0%B2H6/H2
4	Exist	1.0%B2H6/H2